Transmission SIMS: A novel approach to achieving higher secondary ion yields of intact biomolecules



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K. Nakajima et al, APL 104 (2014) 114103.

SIMS: secondary ion mass spectrometry

Excellent lateral and depth resolution Sensitivity is extremely high



Often used for analysis and imaging of biomolecules



D. Jeramie et al, Nature Reviews Microbiology 9, 683.

Transmission SIMS

Sensitivity for large biomolecules is rather poor because biomolecules are easily destroyed by ion impact

in combination with high energy cluster ions, secondary ion yield of intact biomolecule is enhanced and fragment ions are suppressed

OUTLINE

1. Introduction

Analysis and imaging of biomaterials using SIMS

2. Transmission SIMS using 6 MeV Cu⁴⁺

In the forward direction, yield of intact amino acid ion is enhanced but fragment ions are more enhanced

3. Transmission SIMS using 5 MeV C₆₀⁺

Yield of intact amino acid ion is enhanced by one order of magnitude and fragment ions are suppressed in the forward direction

The mechanism of the enhancement and suppression is discussed in terms of deposited-energy distribution at the surface

4. Development of new molecular imaging technique

Transmission SIMS + PEEM

5. Summary

Sensitivity of conventional SIMS is poor for biomolecules





Yield of intact molecular ion is very low Fragment ions are dominant

To improve the sensitivity of biomolecules
1. Use of high energy ions → PDMS, MeV-SIMS
2. Use of cluster ions → Cluster SIMS

Plasma Desorption Mass Spectrometry (PDMS)



D.E. Torgerson et al, Biochem. Biophys. Res. Commun. 60 (1974) 616.

MeV-SIMS: becomes popular for the analysis of biomaterials

6 MeV Cu⁴⁺ \rightarrow animal cells







m/z 79 (PO3) Max counts : 247

H. Yamada et al, Surf. Interface Anal. 43 (2011) 363.

Cluster SIMS: C₆₀ ion



Large yields compared to conventional SIMS Yield increases with impact energy

 \rightarrow further enhancement with MeV C₆₀⁺?

Another possibility to enhance the yield in SIMS

In the conventional SIMS, 2ndary ions emitted in the backward direction are measured



Primary ions can directly transfer their momentum to the target atoms in the forward direction \rightarrow Enhancement of secondary ion yield is expected in the forward direction

MeV ions, cluster ions, transmission geometry \rightarrow Transmission SIMS using MeV C₆₀ ion

Setup: TOF-SIMS with 5 MeV C₆₀ ion



What happens when 5 MeVC₆₀ \rightarrow a-SiN



TEM image lagadiation with SeMe₀V large effect on the target

10nm

Tilt image: 25° C₆₀rton_tShould₀haye Track length ~44 nm Projected range ~190 nm



Cylindrical ion track is produced Density is reduced inside the ion track? \rightarrow HAADF-STEM

10nm

HAADF-STEM: semi-quantitative analysis is possible

HAADF-STEM image



Missing volume ~400 nm³ \rightarrow 3000 atoms! This suggests very large sputtering yield

Sputtering yield measurement using high-resolution RBS



Ballistic collision cascade is negligible \rightarrow Thermal spike plays an important role. Sputtering yield is estimated using unified thermal spike (u-TS) model

Unified thermal spike (u-TS) model

The u-TS model describes temperature evolution using two thermal diffusion equations.

$$C_{e}\frac{\partial T_{e}}{\partial t} = \frac{1}{r}\frac{\partial}{\partial r}\left[rK_{e}\frac{\partial T_{e}}{\partial r}\right] - g(T_{e} - T_{a}) + A(r, v, t)$$
$$C_{a}\frac{\partial T_{a}}{\partial t} = \frac{1}{r}\frac{\partial}{\partial r}\left[rK_{a}\frac{\partial T_{a}}{\partial r}\right] + g(T_{e} - T_{a}) + B(r, t)$$

Both S_e and S_n are included

Thermal evaporation mechanism

P. Sigmund, C. Claussen, J. Appl. Phys. 52 (1981) 990.

$$\Phi_i(T_a(r,t)) = N_i \sqrt{\frac{k_B T_a(r,t)}{2\pi M_i}} exp\left(\frac{-U_i}{k_B T_a(r,t)}\right)$$



Evolution of atomic temperature

M. Toulemonde et al, Phys. Rev. B 83, 054106 (2011).



u-TS model reproduces observed sputtering yield

u-TS model also reproduces observed track radius produced by swift heavy ions as well as C₆₀ ions



Summary: effect of MeV C₆₀ ion impact on materials A very intense thermal spikes are produced



As a result of such a very intense thermal spike,
1) Cylindrical ion tracks are produced: diameter a few nm length several tens nm
2) Extremely high sputtering yield is observed: several thousand atoms/incident ion → large 2ndary ion yield?

SIMS measurement with 6 MeV Cu⁴⁺ ion



6 MeV Cu⁴⁺→ phenylalanine

Compapiesrisobetwith conventionalls and emission



What is the mechanism of enhancement in the forward direction?

Preferential momentum transfer in the forward direction

(2) Charge state dependence of secondary ion yield

The ions transmitted through the sample generally have higher charge states than the incident charge state, as a result, more Seudindary Pons may be emitted SBD 6 Meever the forward direction.

Average exit charge ~ 8.5+



In order to see if the ions of higher charge states really produce more secondary ions, we measured secondary ions in coincidence with the exit charge state. 17

Charge state dependence of secondary ion yield



Enhancement in the forward direction can be explained by the charge state dependence.Preferential momentum transfer does not play a role.The origin of charge state dependence \rightarrow Stopping power dependence18

Stopping power dependence of 2ndary ion yield



In the present case, primary ions lose energy mainly by electronic excitation. Excited electrons transfer their energy to target atoms/molecules and eventually secondary ions are emitted.

6 MeV Cu⁴⁺: forward vs backward (Fragment Ions)



Yield enhancement of fragment ions in the forward direction looks more pronounced than the intact molecular ion

Ratio of forward/backward yield: 6 MeV Cu⁴⁺



Yield enhancement in the forward direction increases with decreasing mass number

This behavior can be explained by a simple model

Why fragment ions are more enhanced ?



Backward emission: 6 MeV Cu⁴⁺ vs 5 MeV C₆₀⁺



O Yield of intact molecular ion is enhanced by using C₆₀ ion

× Yields of fragment ions are much more enhanced

5 MeV C₆₀⁺ : forward vs backward



- **O** Yield of intact molecular ion is enhanced by a factor of 8 in the forward direction
- **O** Yields of fragment ions are suppressed

Ratio of forward/backward yield: 5 MeV C₆₀⁺ vs Cu⁴⁺



In the case of C_{60} ion bombardment, the ratio of forward/ backward yield decreases with decreasing mass number contrary to the monoatomic ion bombardment.

Passage of C₆₀ ion in the sample



For thicker samples, the distribution is wider and so larger enhancement of intact molecular ion and larger suppression of fragment ions are expected. \rightarrow Measurements with samples of various thicknesses were performed.²⁶

Fraction of intact molecular ion vs distribution width



Yield of intact ion increases with increasing width as is expected Maximum yield of intact molecular ion obtained so far is ~ 0.2 ions/incident C₆₀ ion

Can be improved by choosing optimal conditions

Result of peptide: prepared by drip-dry of water solution



Intact peptide molecules are observed. The yield of intact molecular ion is ~ 0.1 ions/incident ion

Ratio of forward/backward yield: 5 MeV C₆₀⁺ vs Cu⁴⁺



Fragmentation is largely suppressed in the forward direction

Molecular imaging using transmission SIMS

after Barney L. Doyle



Just installed in the beam line last week

beam

PEEN

POR-SINIS

PEEM image: test sample



Summary

- ♦ Transmission SIMS measurements were performed using 6 MeV Cu⁴⁺ and 5 MeV C₆₀⁺ ions.
- Under the bombardment of 6 MeV Cu⁴⁺ ions, secondary ion yields of both intact molecules and fragment ions are enhanced in the forward direction.
- Under the bombardment of 5 MeV C₆₀⁺ ions, secondary ion yield of the intact molecules is enhanced in the forward direction while the yield of fragment ions is reduced.
- The observed yield enhancement and reduction can be qualitatively understood by a simple model of secondary ion emission.
- The maximum yield of intact phenylalanine ion is ~ 0.2 ions/incident ion so far and may be improved by choosing optimal conditions.